



# UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE  
United States Patent and Trademark Office  
Address: COMMISSIONER FOR PATENTS  
P.O. Box 1450  
Alexandria, Virginia 22313-1450  
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
-----------------	-------------	----------------------	---------------------	------------------

10/500,716

07/06/2004

Alexander David Scott Ellin

120299

7195

25944 7590 12/04/2012  
OLIFF & BERRIDGE, PLC  
P.O. BOX 320850  
ALEXANDRIA, VA 22320-4850

EXAMINER

HEINRICH, SAMUEL M

ART UNIT

PAPER NUMBER

3742

NOTIFICATION DATE

DELIVERY MODE

12/04/2012

ELECTRONIC

**Please find below and/or attached an Office communication concerning this application or proceeding.**

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail address(es):

OfficeAction25944@oliff.com  
jarmstrong@oliff.com

UNITED STATES PATENT AND TRADEMARK OFFICE

---

BEFORE THE PATENT TRIAL AND APPEAL BOARD

---

*Ex parte* ALEXANDER DAVID SCOTT ELLIN and  
JAMES REYNOLDS HENSHAW

---

Appeal 2010-009287  
Application 10/500,716  
Technology Center 3700

---

1 Before STEVEN D.A. McCARTHY, GAY ANN SPAHN and  
JOHN W. MORRISON, *Administrative Patent Judges*.

McCARTHY, *Administrative Patent Judge*.

DECISION ON APPEAL

2 STATEMENT OF THE CASE

3 The Appellants<sup>1</sup> appeal under 35 U.S.C. § 134 from the Examiner's  
4 final decision rejecting claims 1-36, 42 and 43. The Examiner rejects under  
5 35 U.S.C. § 103(a) claims 1-14, 19-32, 42 and 43 as being unpatentable over

---

<sup>1</sup> The Appellants identify the real party in interest as Renishaw PLC.

1 the Appellants' Admitted Prior Art ("the AAPA"), Michel (DE 196 08 937  
2 A1, publ. Sep. 12, 1996)<sup>2</sup> and Neev (US 6,156,030, issued Dec. 5, 2000);  
3 claims 15-17 and 33-35 as being unpatentable over the AAPA, Michel, Neev  
4 and Gallagher (US 2003/0015672 A1, publ. Jan. 23, 2003); and claims 18  
5 and 36 as being unpatentable over the AAPA, Michel, Neev and Neiheisel  
6 (US 5,736,709, issued Apr. 7, 1998). An oral hearing was held on  
7 November 6, 2012. We have jurisdiction under 35 U.S.C. § 6(b).

8 We REVERSE.

9 Claims 1 and 19 are independent. Claim 1 is illustrative:

10 1. A method of producing precision  
11 marks for a metrological scale, employing  
12 apparatus including:

13 a scale substrate to be marked  
14 at repeated instants by a laser and  
15 thereby forming a metrological scale;

16 a laser operable so as to provide  
17 light pulses for forming scale  
18 markings at the substrate;

19 a displacement device for  
20 causing relative displacement between  
21 the substrate and the location at which  
22 the light is incident on the substrate;  
23 and

24 a controller for controlling the  
25 relative displacement and the laser,

26 the method comprising the steps, in any  
27 suitable order, of:

28 operating the displacement  
29 mechanism so as to cause relative

---

<sup>2</sup> References to Michel will be to the Official Translation prepared by FLS, Inc. in or about November 2009.

1 displacement between the substrate  
2 and the light;

3 using the controller to control  
4 the relative displacement and to  
5 operate the laser so as to produce light  
6 pulses at the substrate;

7 characterised in that:

8 the laser produces a plurality of  
9 ultra-short pulses<sup>3</sup> of a fluence at the  
10 substrate such that the metrological  
11 scale marks are formed by laser  
12 ablation, wherein the plurality of  
13 ultra-short pulses have a duration such  
14 that the scale markings are formed on  
15 the scale substrate by a laser ablation  
16 mechanism in which the molten stage  
17 is omitted.

18 Independent claim 19 recites an apparatus for producing precision marks for  
19 a metrological scale including, *inter alia*, a laser,

20 characterised in that the pulses of light produced  
21 by the laser are ultra-short pulses of a fluence at  
22 the substrate such that the metrological scale  
23 marks are formed by laser ablation, wherein the  
24 plurality of ultra-short output pulses have a  
25 duration such that the scale markings are formed  
26 on the scale substrate by a laser ablation  
27 mechanism in which the molten stage is omitted.

28 The AAPA appears primarily at page 1, line 31 through page 2, line  
29 29 of the Specification. The Examiner summarizes the AAPA as describing  
30 “[1] known production of measurement scale using a laser, [2] use of a  
31 reference to correct deficiencies, [3] marking perpendicular to the laser

---

<sup>3</sup> The Specification defines “ultra-short pulses” as pulses having pulse lengths below approximately 4 picoseconds. (*See Spec. 2, ll. 21-27*).

1 travel direction, and [4] known laser solid to gaseous state ablation  
2 performed at below 4 picoseconds pulse length.” (Ans. 4 (reference  
3 numerals added)). The Appellants’ Specification supports all four of the  
4 Examiner’s findings. (*See* Spec. 1, ll. 31-32; Spec. 1, l. 34 – 2, l. 1; Spec. 2,  
5 ll. 6-8; and Spec. 2, ll. 14-17 and 21-29). On the other hand, the Examiner  
6 finds that the “AAPA does not describe forming a scale by laser ablation  
7 (direct solid to vapor phase transition).” (Ans. 4).

8 Neev describes the use of a laser to ablate material. (Neev, col. 7, ll.  
9 7-8). In fact, both the AAPA and Neev describe laser ablation mechanisms  
10 using high energy, ultra-short pulses (that is, pulses of length less than 4  
11 picoseconds). Neither suggests exploiting this mechanism to produce scale  
12 markings, however. In particular, the only examples of materials which  
13 Neev appears to suggest ablating with a laser producing a pulse width of 4  
14 picoseconds or less are biological tissues. (*See, e.g.*, Neev, col. 28, ll. 56-63  
15 and col. 29, ll. 20-34; *see also id.*, col. 5, ll. 3-18).

16 Michel describes forming tags (that is, index markings) using high-  
17 energy laser from an excimer laser. (Michel 2, l. 20 – 3, l. 2). Michel  
18 discloses applying the tag (or scale marked) layer T<sub>1</sub> “in the usual way” as a  
19 gold layer on a steel strip as S<sub>1</sub> or, alternatively, on a highly polished surface  
20 T<sub>2</sub> on the steel strip. (Michel 3, ll. 16-20). Michel teaches that:

21 The high-energy radiation can be generated with  
22 the use of the previously mentioned excimer laser.  
23 For manufacturing the separating structure [or  
24 divisional structure] TS<sub>1</sub> or TS<sub>2</sub> in the form of a  
25 grid, the highly reflective surface of the gold layer  
26 T<sub>1</sub> or the polished surface T<sub>2</sub> of the substrate S<sub>2</sub> is  
27 melted with the use of short laser pulses with a  
28 duration of about 20 ns [that is, about 20,000  
29 picoseconds], after which, in the pulse pause, the

1 surface  $T_1$ ,  $T_2$  immediately solidifies again. *In*  
2 *order to prevent energy dissipation from the*  
3 *processing area during the duration of the laser*  
4 *pulse, pulses of a clearly shorter duration can be*  
5 *used.* The solidified melt has a different roughness  
6 and thus different optical properties than the highly  
7 reflective surfaces  $T_1$ ,  $T_2$  and a separating structure  
8  $TS_1$ ,  $TS_2$  with reduced reflectivity develops.

9 (Michel 3, l. 21 – 4, l. 7 (italics added)).

10 In other words, Michel teaches forming scale markings by melting  
11 and re-solidifying portions of the polished surface of a marked layer in order  
12 to change the optical properties of the marked layer. (See Michel 3, l. 21 –  
13 4, l. 7 (italics added)). On the other hand, the Examiner cites the AAPA and  
14 Neev as teaching the use of lasers to ablate materials. (Ans. 4). Neev, in  
15 fact, suggests that one advantage of Neev's teachings is that melting and  
16 boiling are minimized. (See, e.g., Neev, col. 24, ll. 10-15).

17 As the Appellants point out, Michel appears to teach the desirability  
18 of what, in other contexts, might have been viewed as product defects. (See  
19 Br. 16). In view of these differences, the Examiner's conclusion that the  
20 "use of a low thermal transfer to the workpiece by performing ultra-short  
21 pulse laser ablation would have been obvious at the time applicant's  
22 invention was made to a person having ordinary skill in the art in order to  
23 minimize the heat affected zone (HAZ) and thereby reduce product defects"  
24 (Ans. 4) is not persuasive.

25 Based on this reasoning, we do not sustain the rejection of claims 1-14  
26 and 42 under § 103(a) as being unpatentable over the AAPA, Michel and  
27 Neev. In addition, the Examiner has not provided reasoning with some  
28 rational underpinning to show that one of ordinary skill would have reason  
29 to provide an apparatus for producing precision marks for a metrological

1 scale with a laser capable of producing ultra-short pulses, we do not sustain  
2 the rejection of claims 19-32 and 43 under § 103(a) as being unpatentable  
3 over the AAPA, Michel and Neev.

4 With respect to the rejection of claims 15-17 and 33-35, the Examiner  
5 finds that “[d]isplacement is described by Gallagher.” (Ans. 5). The  
6 Examiner concludes that the “the use thereof in displacement for laser  
7 ablation of marks” would have been obvious “because automated movement  
8 control provides controlled regular ablation.” (*Id.*) This finding and  
9 reasoning does not remedy the deficiencies in the combined teachings of the  
10 AAPA, Michel and Neev as applied to independent claims 1 and 19. We do  
11 not sustain the rejection of claims 15-17 and 33-35 under § 103(a) as being  
12 unpatentable over the AAPA, Michel, Neev and Gallagher.

13 With respect to the rejection of claims 18 and 36, the Examiner finds  
14 that “Neiheisel describes laser ablation and shows (Figure 10b) the well  
15 known elliptical spot.” (Ans. 6). The Examiner concludes that the  
16 “elliptical spot” would have been obvious “because it provides a narrower  
17 profile for precision shaped etching.” (*Id.*) This finding and reasoning does  
18 not remedy the deficiencies in the combined teachings of the AAPA, Michel  
19 and Neev as applied to independent claims 1 and 19. We do not sustain the  
20 rejection of claims 15-17 and 33-35 under § 103(a) as being unpatentable  
21 over the AAPA, Michel, Neev and Neiheisel.

22 DECISION

23 We REVERSE the Examiner’s decision rejecting claims 1-36, 42 and  
24 43.

25 REVERSED

26 Klh